Anjana Devi

List of Publications by Year
in descending order

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217 papers	5,108 citations	76294 40 h-index	149623 56 g-index
227 all docs	227 docs citations	227 times ranked	5970 citing authors

#	Article	IF	Citations
1	Molecular Permeation in Freestanding Bilayer Silica. Nano Letters, 2022, 22, 1287-1293.	4.5	14
2	Role of Anionic Backbone in NHCâ€Stabilized Coinage Metal Complexes: New Precursors for Atomic Layer Deposition**. Chemistry - A European Journal, 2022, 28, .	1.7	5
3	Influence of surface activation on the microporosity of PEâ€CVD and PEâ€ALD SiO_x thin films on PDMS. Plasma Processes and Polymers, 2022, 19, .	1.6	5
4	Influence of different ester side groups in polymers on the vapor phase infiltration with trimethyl aluminum. Dalton Transactions, 2022, 51, 1384-1394.	1.6	3
5	Atomic/molecular layer deposition of cerium(<scp>iii</scp>) hybrid thin films using rigid organic precursors. Dalton Transactions, 2022, 51, 5603-5611.	1.6	3
6	Bendable Polycrystalline and Magnetic CoFe₂O₄ Membranes by Chemical Methods. ACS Applied Materials & Interfaces, 2022, 14, 12845-12854.	4.0	17
7	Ferromagnetic Europium Sulfide Thin Films: Influence of Precursors on Magneto-Optical Properties. Chemistry of Materials, 2022, 34, 152-164.	3.2	4
8	Highly sensitive and stable MEMS acetone sensors based on well-designed Î±-Fe2O3/C mesoporous nanorods. Journal of Colloid and Interface Science, 2022, 622, 156-168.	5.0	17
9	Rational Development of Guanidinate and Amidinate Based Cerium and Ytterbium Complexes as Atomic Layer Deposition Precursors: Synthesis, Modeling, and Application. Chemistry - A European Journal, 2021, 27, 4913-4926.	1.7	11
10	Atomic layer deposition of dielectric Y₂O₃ thin films from a homoleptic yttrium formamidinate precursor and water. RSC Advances, 2021, 11, 2565-2574.	1.7	15
11	Fabrication of Gd_xFe_yO_z films using an atomic layer deposition-type approach. CrystEngComm, 2021, 23, 730-740.	1.3	4
12	A study on the influence of ligand variation on formamidinate complexes of yttrium: new precursors for atomic layer deposition of yttrium oxide. Dalton Transactions, 2021, 50, 12944-12956.	1.6	8
13	Investigation of an atomicâ€layerâ€deposited Al₂O₃ diffusion barrier between Pt and Si for the use in atomic scale atom probe tomography studies on a combinatorial processing platform. Surface and Interface Analysis, 2021, 53, 727-733.	0.8	1
14	(tBuN)SiMe2NMe2â€"A new N,Nâ€²-Î²2-monoanionic ligand for atomic layer deposition precursors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 032409.	0.9	2
15	Cobalt Metal ALD: Understanding the Mechanism and Role of Zinc Alkyl Precursors as Reductants for Low-Resistivity Co Thin Films. Chemistry of Materials, 2021, 33, 5045-5057.	3.2	16
16	Atomic Layer Deposition of Copper Metal Films from Cu(acac)₂ and Hydroquinone Reductant. Advanced Engineering Materials, 2021, 23, 2100446.	1.6	7
17	Direct liquid injection chemical vapor deposition of ZrO2 films from a heteroleptic Zr precursor: interplay between film characteristics and corrosion protection of stainless steel. Journal of Materials Research and Technology, 2021, 13, 1599-1614.	2.6	16
18	Chemical Vapor Deposition of Cobalt and Nickel Ferrite Thin Films: Investigation of Structure and Pseudocapacitive Properties. Advanced Materials Interfaces, 2021, 8, 2100949.	1.9	6

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19	Facile Chemical Route to Prepare Water Soluble Epitaxial Sr₃Al₂O₆ Sacrificial Layers for Freeâ€Standing Oxides. Advanced Materials Interfaces, 2021, 8, 2001643.	1.9	13
20	CVD grown GaSb_xN_{1â^'x} films as visible-light active photoanodes. Dalton Transactions, 2021, 50, 14832-14841.	1.6	0
21	Sensing and electrocatalytic activity of tungsten disulphide thin films fabricated via metalâ€"organic chemical vapour deposition. Journal of Materials Chemistry C, 2021, 9, 10254-10265.	2.7	8
22	Co(II) Amide, Pyrrolate, and Aminopyridinate Complexes: Assessment of their Manifold Structural Chemistry and Thermal Properties**. European Journal of Inorganic Chemistry, 2021, 2021, 5119-5136.	1.0	2
23	Comparative Study of Photocarrier Dynamics in CVD-deposited CuWO₄, CuO, and WO₃ Thin Films for Photoelectrocatalysis. Zeitschrift Fur Physikalische Chemie, 2020, 234, 699-717.	1.4	11
24	A carbene stabilized precursor for the spatial atomic layer deposition of copper thin films. Chemical Communications, 2020, 56, 13752-13755.	2.2	12
25	Ein seltenes Lowâ€Spinâ€Co IV â€Bis(Î²â€silyldiamid) mit hoher thermischer StabilitÃt: Sterische Erzwingung einer Dublettkonfiguration. Angewandte Chemie, 2020, 132, 14242-14246.	1.6	4
26	A new metalorganic chemical vapor deposition process for MoS₂ with a 1,4-diazabutadienyl stabilized molybdenum precursor and elemental sulfur. Dalton Transactions, 2020, 49, 13462-13474.	1.6	12
27	Study on Structural and Thermal Characteristics of Heteroleptic Yttrium Complexes as Potential Precursors for Vapor Phase Deposition. European Journal of Inorganic Chemistry, 2020, 2020, 3587-3596.	1.0	12
28	A Rare Lowâ€Spin Co IV Bis(Î²â€silyldiamide) with High Thermal Stability: Steric Enforcement of a Doublet Configuration. Angewandte Chemie - International Edition, 2020, 59, 14138-14142.	7.2	11
29	Hierarchical highly ordered SnO2 nanobowl branched ZnO nanowires for ultrasensitive and selective hydrogen sulfide gas sensing. Microsystems and Nanoengineering, 2020, 6, 30.	3.4	47
30	Additive-free spin coating of tin oxide thin films: synthesis, characterization and evaluation of tin Î²-ketoiminates as a new precursor class for solution deposition processes. Dalton Transactions, 2020, 49, 10755-10764.	1.6	8
31	Tuning Coordination Geometry of Nickel Ketoiminates and Its Influence on Thermal Characteristics for Chemical Vapor Deposition of Nanostructured NiO Electrocatalysts. Inorganic Chemistry, 2020, 59, 10059-10070.	1.9	14
32	Atomic scale growth of GdFeO3 perovskite thin films. Thin Solid Films, 2020, 698, 137848.	0.8	13
33	From Precursor Chemistry to Gas Sensors: Plasmaâ€Enhanced Atomic Layer Deposition Process Engineering for Zinc Oxide Layers from a Nonpyrophoric Zinc Precursor for Gas Barrier and Sensor Applications. Small, 2020, 16, e1907506.	5.2	13
34	PEALD of HfO₂ Thin Films: Precursor Tuning and a New Near-Ambient-Pressure XPS Approach to in Situ Examination of Thin-Film Surfaces Exposed to Reactive Gases. ACS Applied Materials & Interfaces, 2019, 11, 28407-28422.	4.0	21
35	Monitoring Surface Stoichiometry, Work Function and Valance Band of Tungsten Oxide (WO3), Molybdenum Oxide (MoO3) and Tin Oxide (SnO2) Thin Films as a Function of Temperature and Oxygen Partial Pressure with Advanced Surface Sensitive Techniques for Chemical Sensing Applications. Proceedings (mdpi), 2019, 14, 27.	0.2	2
36	Atomic layer deposition of functional multicomponent oxides. APL Materials, 2019, 7, .	2.2	45

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37	Up-converting ALD/MLD thin films with Yb3+, Er3+ in amorphous organic framework. Journal of Luminescence, 2019, 213, 310-315.	1.5	13
38	Potential Precursor Alternatives to the Pyrophoric Trimethylaluminium for the Atomic Layer Deposition of Aluminium Oxide. Chemistry - A European Journal, 2019, 25, 7489-7500.	1.7	8
39	Fabrication of heterostructured p-CuO/n-SnO2 core-shell nanowires for enhanced sensitive and selective formaldehyde detection. Sensors and Actuators B: Chemical, 2019, 290, 233-241.	4.0	106
40	How water flips at charged titanium dioxide: an SFG-study on the waterâ€“TiO₂ interface. Physical Chemistry Chemical Physics, 2019, 21, 8956-8964.	1.3	13
41	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of Tin(IV) Oxide from a Functionalized Alkyl Precursor: Fabrication and Evaluation of SnO₂-Based Thin-Film Transistor Devices. ACS Applied Materials & Interfaces, 2019, 11, 3169-3180.	4.0	33
42	Luminescent Nd₂S₃ thin films: a new chemical vapour deposition route towards rare-earth sulphides. Dalton Transactions, 2019, 48, 2926-2938.	1.6	7
43	Investigating Zinc Ketoiminates as a New Class of Precursors for Solution Deposition of ZnO Thin Films. Journal of Nanoscience and Nanotechnology, 2019, 19, 867-876.	0.9	3
44	Validation of a Terminally Amino Functionalized Tetraâ€Alkyl Sn(IV) Precursor in Metalâ€“Organic Chemical Vapor Deposition of SnO 2 Thin Films: Study of Film Growth Characteristics, Optical, and Electrical Properties. Advanced Materials Interfaces, 2019, 6, 1801540.	1.9	9
45	CVD-grown copper tungstate thin films for solar water splitting. Journal of Materials Chemistry A, 2018, 6, 10206-10216.	5.2	25
46	Rational Development of Cobalt Î²-Ketoiminate Complexes: Alternative Precursors for Vapor-Phase Deposition of Spinel Cobalt Oxide Photoelectrodes. Inorganic Chemistry, 2018, 57, 5133-5144.	1.9	14
47	Ultrasound-mediated deposition and cytocompatibility of apatite-like coatings on magnesium alloys. Surface and Coatings Technology, 2018, 345, 167-176.	2.2	4
48	PEALD of SiO₂ and Al₂O₃ Thin Films on Polypropylene: Investigations of the Film Growth at the Interface, Stress, and Gas Barrier Properties of Dyads. ACS Applied Materials & Interfaces, 2018, 10, 7422-7434.	4.0	37
49	Manganese(II) Molecular Sources for Plasma-Assisted CVD of Mn Oxides and Fluorides: From Precursors to Growth Process. Journal of Physical Chemistry C, 2018, 122, 1367-1375.	1.5	34
50	Molecular engineering of Ga-ketoiminates: synthesis, structure and evaluation as precursors for the additive-free spin-coated deposition of gallium oxide thin films. New Journal of Chemistry, 2018, 42, 3196-3210.	1.4	6
51	Fabrication of zinc-dicarboxylate- and zinc-pyrazolate-carboxylate-framework thin films through vapourâ€“solid deposition. Dalton Transactions, 2018, 47, 14179-14183.	1.6	13
52	Tailored Î²â€Ketoiminato Complexes of Iron: Synthesis, Characterization, and Evaluation towards Solutionâ€Based Deposition of Iron Oxide Thin Films. European Journal of Inorganic Chemistry, 2018, 2018, 1824-1833.	1.0	7
53	Direct Growth of MoS₂ and WS₂ Layers by Metal Organic Chemical Vapor Deposition. Advanced Materials Interfaces, 2018, 5, 1800140.	1.9	52
54	A combinatorial approach to enhance barrier properties of thin films on polymers: Seeding and capping of PECVD thin films by PEALD. Plasma Processes and Polymers, 2018, 15, 1700209.	1.6	12

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55	Water assisted atomic layer deposition of yttrium oxide using tris(N,Nâ€²-diisopropyl-2-dimethylamido-guanidinato) yttrium(<scp>iii</scp>): process development, film characterization and functional properties. RSC Advances, 2018, 8, 4987-4994.	1.7	38
56	Analysis of dispersive interactions at polymer/TiAlN interfaces by means of dynamic force spectroscopy. Physical Chemistry Chemical Physics, 2018, 20, 180-190.	1.3	7
57	Atomic Layer Deposition of Nickel on ZnO Nanowire Arrays for High-Performance Supercapacitors. ACS Applied Materials & Interfaces, 2018, 10, 468-476.	4.0	30
58	Atomic/molecular layer deposition of Cuâ€"organic thin films. Dalton Transactions, 2018, 47, 15791-15800.	1.6	14
59	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. Chemistry of Materials, 2018, 30, 8690-8701.	3.2	26
60	Ein Nâ€heterocyclischer Carbenkomplex des Silbers fÃ¼r die plasmaunterstÃ¼tzte rÃumlich getrennte Atomlagenabscheidung dÃ¼nner Silberschichten bei AtmosphÃrendruck. Angewandte Chemie, 2018, 130, 16458-16462.	1.6	2
61	An Nâ€Heterocyclic Carbene Based Silver Precursor for Plasmaâ€Enhanced Spatial Atomic Layer Deposition of Silver Thin Films at Atmospheric Pressure. Angewandte Chemie - International Edition, 2018, 57, 16224-16227.	7.2	22
62	Designing Stability into Thermally Reactive Plumbylenes. Inorganic Chemistry, 2018, 57, 8218-8226.	1.9	18
63	Synthesis of rare-earth metal and rare-earth metal-fluoride nanoparticles in ionic liquids and propylene carbonate. Beilstein Journal of Nanotechnology, 2018, 9, 1881-1894.	1.5	18
64	Transport mechanisms through PE-CVD coatings: influence of temperature, coating properties and defects on permeation of water vapour. Journal Physics D: Applied Physics, 2017, 50, 085203.	1.3	4
65	Synthesis and evaluation of new copper ketoiminate precursors for a facile and additive-free solution-based approach to nanoscale copper oxide thin films. Dalton Transactions, 2017, 46, 2670-2679.	1.6	17
66	Photoactive Zinc Ferrites Fabricated via Conventional CVD Approach. ACS Sustainable Chemistry and Engineering, 2017, 5, 2917-2926.	3.2	41
67	Atomic/molecular layer deposition of hybrid inorganicâ€"organic thin films from erbium guanidinate precursor. Journal of Materials Science, 2017, 52, 6216-6224.	1.7	17
68	Nanostructured Fe₂O₃ Processing via Waterâ€Assisted ALD and Lowâ€Temperature CVD from a Versatile Iron Ketoiminate Precursor. Advanced Materials Interfaces, 2017, 4, 1700155.	1.9	28
69	Influence of PE-CVD and PE-ALD on defect formation in permeation barrier films on PET and correlation to atomic oxygen fluence. Journal Physics D: Applied Physics, 2017, 50, 235201.	1.3	11
70	Spectroscopic investigation of wheat grains (Triticum aestivum) infected by wheat seed gall nematodes (Anguina tritici). Biocatalysis and Agricultural Biotechnology, 2017, 9, 58-66.	1.5	15
71	New amidinate complexes of indium(<scp>iii</scp>): promising CVD precursors for transparent and conductive In₂O₃ thin films. Dalton Transactions, 2017, 46, 10220-10231.	1.6	23
72	Review Article: Recommended reading list of early publications on atomic layer depositionâ€"Outcome of the â€œVirtual Project on the History of ALDâ€. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	65

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73	Unearthing [3â€(Dimethylamino)propyl]aluminium(III) Complexes as Novel Atomic Layer Deposition (ALD) Precursors for Al₂O₃: Synthesis, Characterization and ALD Process Development. Chemistry - A European Journal, 2017, 23, 10768-10772.	1.7	15
74	Integrating AlN with GdN Thin Films in an in Situ CVD Process: Influence on the Oxidation and Crystallinity of GdN. ACS Applied Materials & Interfaces, 2017, 9, 27036-27044.	4.0	8
75	Low temperature growth of gallium oxide thin films via plasma enhanced atomic layer deposition. Dalton Transactions, 2017, 46, 16551-16561.	1.6	56
76	Molecular Engineering of Mn^{II} Diamine Diketonate Precursors for the Vapor Deposition of Manganese Oxide Nanostructures. Chemistry - A European Journal, 2017, 23, 17954-17963.	1.7	33
77	Low-Temperature Atomic Layer Deposition of Low-Resistivity Copper Thin Films Using Cu(dmap)₂ and Tertiary Butyl Hydrazine. Chemistry of Materials, 2017, 29, 6502-6510.	3.2	27
78	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. Chemistry of Materials, 2017, 29, 5796-5805.	3.2	43
79	Effects of Post Annealing Treatments on the Interfacial Chemical Properties and Band Alignment of AlN/Si Structure Prepared by Atomic Layer Deposition. Nanoscale Research Letters, 2017, 12, 102.	3.1	13
80	A cobalt(ii)heteroarylalkenolate precursor for homogeneous Co3O4 coatings by atomic layer deposition. Dalton Transactions, 2017, 46, 12996-13001.	1.6	9
81	Temperature-dependent transport mechanisms through PE-CVD coatings: comparison of oxygen and water vapour. Journal Physics D: Applied Physics, 2017, 50, 395302.	1.3	3
82	Systematic molecular engineering of Zn-ketoiminates for application as precursors in atomic layer depositions of zinc oxide. Dalton Transactions, 2016, 45, 19012-19023.	1.6	17
83	Ideal parameter to assess efficacy of fixed functional appliance: angular or linear?. European Journal of Orthodontics, 2016, 38, 337-337.	1.1	0
84	Letters From Our Readers. Angle Orthodontist, 2016, 86, 1058-1058.	1.1	0
85	Rapid palatal expansion, with and without alternating constriction. American Journal of Orthodontics and Dentofacial Orthopedics, 2016, 149, 779-780.	0.8	0
86	An efficient PE-ALD process for TiO₂ thin films employing a new Ti-precursor. Journal of Materials Chemistry C, 2016, 4, 1057-1065.	2.7	24
87	Metalâ€organic CVD of Y₂O₃ Thin Films using Yttrium trisâ€amidinates. Chemical Vapor Deposition, 2015, 21, 335-342.	1.4	8
88	MOCVD of TiO₂ thin films from a modified titanium alkoxide precursor. Physica Status Solidi (A) Applications and Materials Science, 2015, 212, 1563-1570.	0.8	7
89	Nanostructured Er₂O₃ Thin Films Grown by Metalorganic Chemical Vapour Deposition. Journal of Nanoscience and Nanotechnology, 2014, 14, 5095-5102.	0.9	7
90	Preface to the CVD Special Issue: Atomicâ€Scaleâ€Engineered Materials (ASEM). Chemical Vapor Deposition, 2014, 20, 186-188.	1.4	0

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91	Atomic-scale engineering of multifunctional nano-sized materials and films. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 249-250.	0.8	0
92	MOCVD of TiO₂ Thin Films using a Heteroleptic Titanium Complex: Precursor Evaluation and Investigation of Optical, Photoelectrochemical and Electrical Properties. Chemical Vapor Deposition, 2014, 20, 224-233.	1.4	5
93	Surface Decoration of Ïµâ€Fe₂O₃ Nanorods by CuO Via a Twoâ€Step CVD/Sputtering Approach**. Chemical Vapor Deposition, 2014, 20, 313-319.	1.4	11
94	<scp>MOCVD</scp> of tungsten nitride thin films: Comparison of precursor performance and film characteristics. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 260-266.	0.8	8
95	Investigation of Optical, Electrical, and Mechanical Properties of MOCVDâ€grown ZrO₂ Films. Chemical Vapor Deposition, 2014, 20, 320-327.	1.4	6
96	Electrical and optical properties of TiO₂ thin films prepared by plasmaâ€enhanced atomic layer deposition. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 416-424.	0.8	41
97	Tailoring iron(<scp>III</scp>) oxide nanomorphology by chemical vapor deposition: Growth and characterization. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 316-322.	0.8	12
98	Low Temperature Stabilization of Nanoscale Epitaxial Spinel Ferrite Thin Films by Atomic Layer Deposition. Advanced Functional Materials, 2014, 24, 5368-5374.	7.8	47
99	Novel Î²-ketoiminato complexes of zirconium: synthesis, characterization and evaluation for solution based processing of ZrO₂thin films. Dalton Transactions, 2014, 43, 2384-2396.	1.6	6
100	Indium-tris-guanidinates: a promising class of precursors for water assisted atomic layer deposition of In₂O₃thin films. Dalton Transactions, 2014, 43, 937-940.	1.6	31
101	Atomic Layer Deposition of TiO₂ and ZrO₂ Thin Films Using Heteroleptic Guanidinate Precursors. Chemical Vapor Deposition, 2014, 20, 209-216.	1.4	9
102	Recent Advances Using Guanidinate Ligands for Chemical Vapour Deposition (CVD) and Atomic Layer Deposition (ALD) Applications. Australian Journal of Chemistry, 2014, 67, 989.	0.5	32
103	Growth and Crystallization of TiO₂Thin Films by Atomic Layer Deposition Using a Novel Amido Guanidinate Titanium Source and Tetrakis-dimethylamido-titanium. Chemistry of Materials, 2013, 25, 2934-2943.	3.2	75
104	â€˜Old Chemistriesâ€™ for new applications: Perspectives for development of precursors for MOCVD and ALD applications. Coordination Chemistry Reviews, 2013, 257, 3332-3384.	9.5	137
105	Atomic layer deposition of Er2O3 thin films from Er tris-guanidinate and water: process optimization, film analysis and electrical properties. Journal of Materials Chemistry C, 2013, 1, 3939.	2.7	18
106	Transition metal nitride thin films grown by MOCVD using amidinato based complexes [M(NtBu)2{(iPrN)2CMe}2] (M=Mo, W) as precursors. Surface and Coatings Technology, 2013, 230, 130-136.	2.2	23
107	A Zâ€²=6 crystal structure of (E)-N,Nâ€²-dicyclohexylacetamidine. Journal of Molecular Structure, 2013, 1031, 239-245.	1.8	4
108	Homoleptic Gadolinium Amidinates as Precursors for MOCVD of Oriented Gadolinium Nitride (GdN) Thin Films. Inorganic Chemistry, 2013, 52, 286-296.	1.9	24

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109	[Zr(NEtMe)₂(guan-NEtMe)₂] as a Novel Atomic Layer Deposition Precursor: ZrO₂ Film Growth and Mechanistic Studies. Chemistry of Materials, 2013, 25, 3088-3095.	3.2	23
110	Intrinsic Nitrogenâ€doped CVDâ€grown TiO₂ Thin Films from Allâ€Nâ€coordinated Ti Precursors for Photoelectrochemical Applications. Chemical Vapor Deposition, 2013, 19, 45-52.	1.4	32
111	Strain-induced phase transitions in epitaxial NaNbO₃thin films grown by metalâ€"organic chemical vapour deposition. Journal of Applied Crystallography, 2012, 45, 1015-1023.	1.9	40
112	Design, synthesis and antimicrobial evaluation of novel 1-benzyl 2-butyl-4-chloroimidazole embodied 4-azafluorenones via molecular hybridization approach. Bioorganic and Medicinal Chemistry Letters, 2012, 22, 7475-7480.	1.0	35
113	Influence of process parameters on the crystallinity, morphology and composition of tungsten oxide-based thin films grown by metalorganic chemical vapor deposition. Thin Solid Films, 2012, 522, 11-16.	0.8	11
114	Î²-Fe₂O₃nanomaterials from an iron(<scp>ii</scp>) diketonate-diamine complex: a study from molecular precursor to growth process. Dalton Transactions, 2012, 41, 149-155.	1.6	63
115	Sc2O3, Er2O3, and Y2O3 thin films by MOCVD from volatile guanidinate class of rare-earth precursors. Dalton Transactions, 2012, 41, 13936.	1.6	40
116	Microgradient-Heaters As Tools for High-Throughput Experimentation. ACS Combinatorial Science, 2012, 14, 531-536.	3.8	4
117	Fabrication of ZrO₂ and ZrN Films by Metalorganic Chemical Vapor Deposition Employing New Zr Precursors. Crystal Growth and Design, 2012, 12, 5079-5089.	1.4	31
118	Atomic Layer Deposition of Gd₂O₃ and Dy₂O₃: A Study of the ALD Characteristics and Structural and Electrical Properties. Chemistry of Materials, 2012, 24, 651-658.	3.2	47
119	Ag/ZnO nanomaterials as high performance sensors for flammable and toxic gases. Nanotechnology, 2012, 23, 025502.	1.3	48
120	Surfactant-Induced Nonhydrolytic Synthesis of Phase-Pure ZrO₂ Nanoparticles from Metalâ€"Organic and Oxocluster Precursors. Chemistry of Materials, 2012, 24, 4274-4282.	3.2	26
121	Co₃O₄/ZnO Nanocomposites: From Plasma Synthesis to Gas Sensing Applications. ACS Applied Materials & Interfaces, 2012, 4, 928-934.	4.0	141
122	CuO/ZnO Nanocomposite Gas Sensors Developed by a Plasmaâ€Assisted Route. ChemPhysChem, 2012, 13, 2342-2348.	1.0	55
123	Rare-earth substituted HfO2 thin films grown by metalorganic chemical vapor deposition. Thin Solid Films, 2012, 520, 4512-4517.	0.8	9
124	Atomic Layer Deposition of HfO₂ Thin Films Employing a Heteroleptic Hafnium Precursor. Chemical Vapor Deposition, 2012, 18, 27-35.	1.4	22
125	Strongly oriented Co3O4 thin films on MgO(100) and MgAl2O4(100) substrates by PE-CVD. CrystEngComm, 2011, 13, 3670.	1.3	26
126	Evaluation of Homoleptic Guanidinate and Amidinate Complexes of Gadolinium and Dysprosium for MOCVD of Rare-Earth Nitride Thin Films. Chemistry of Materials, 2011, 23, 1430-1440.	3.2	42

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127	F-Doped Co₃O₄ Photocatalysts for Sustainable H₂ Generation from Water/Ethanol. Journal of the American Chemical Society, 2011, 133, 19362-19365.	6.6	171
128	Malonate complexes of dysprosium: synthesis, characterization and application for LI-MOCVD of dysprosium containing thin films. Dalton Transactions, 2011, 40, 62-78.	1.6	21
129	Atomic Vapor Deposition Approach to In₂O₃ Thin Films. Journal of Nanoscience and Nanotechnology, 2011, 11, 8094-8100.	0.9	8
130	Growth of epitaxial sodium-bismuth-titanate films by metal-organic chemical vapor phase deposition. Thin Solid Films, 2011, 520, 239-244.	0.8	11
131	Plasma enhanced-CVD of undoped and fluorine-doped Co3O4 nanosystems for novel gas sensors. Sensors and Actuators B: Chemical, 2011, 160, 79-86.	4.0	56
132	Plasma-assisted synthesis of Ag/ZnO nanocomposites: First example of photo-induced H2 production and sensing. International Journal of Hydrogen Energy, 2011, 36, 15527-15537.	3.8	79
133	MOCVD of ZnO Films from Bis(Ketoiminato)Zn(II) Precursors: Structure, Morphology and Optical Properties. Chemical Vapor Deposition, 2011, 17, 155-161.	1.4	27
134	Basic investigation of HfO2 based metalâ€“insulatorâ€“metal diodes. Thin Solid Films, 2011, 519, 5796-5799.	0.8	8
135	Influence of Na on the structure of Bi4Ti3O12 films deposited by liquid-delivery spin MOCVD. Thin Solid Films, 2011, 519, 5754-5759.	0.8	6
136	Plasma Processing of Nanomaterials: Emerging Technologies for Sensing and Energy Applications. Journal of Nanoscience and Nanotechnology, 2011, 11, 8206-8213.	0.9	27
137	p-Co3O4/n-ZnO, Obtained by PECVD, Analyzed by X-ray Photoelectron Spectroscopy. Surface Science Spectra, 2011, 18, 36-45.	0.3	8
138	High Mobility ZnO thin film transistors using the novel deposition of high-k dielectrics. Materials Research Society Symposia Proceedings, 2011, 1315, 1.	0.1	2
139	ZnO Nanorod Arrays by Plasmaâ€Enhanced CVD for Lightâ€Activated Functional Applications. ChemPhysChem, 2010, 11, 2337-2340.	1.0	40
140	Growth and Characterization of Tiâ€Taâ€O Thin Films on Si Substrates by Liquid Injection MOCVD for Highâ€k Applications from Modified Titanium and Tantalum Precursors. Chemical Vapor Deposition, 2010, 16, 157-165.	1.4	13
141	Volatile, Monomeric, and Fluorineâ€Free Precursors for the Metal Organic Chemical Vapor Deposition of Zinc Oxide. European Journal of Inorganic Chemistry, 2010, 2010, 1366-1372.	1.0	37
142	Heteroleptic Guanidinateâ€and Amidinateâ€Based Complexes of Hafnium as New Precursors for MOCVD of HfO₂. European Journal of Inorganic Chemistry, 2010, 2010, 1679-01688.	1.0	28
143	Depositions of SrRuO3 thin films on oxide substrates with liquid-delivery spin MOCVD. Thin Solid Films, 2010, 518, 4675-4679.	0.8	8
144	1D ZnO nano-assemblies by Plasma-CVD as chemical sensors for flammable and toxic gases. Sensors and Actuators B: Chemical, 2010, 149, 1-7.	4.0	169

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